MDPpro

Mono- and Multi-crystalline wafer and brick lifetime measurement device

for routine quality control and sophisticated material research & development

Si | compound semiconductors | oxides | wide bandgap materials | perovskites | epitaxial layers

[CdTe | InP | ZnS | SiC | GaAs | GaN | Ge]



Routine Lifetime Measurement Quality Control & Inspection

Best throughput: >240 bricks/day or >720 wafers/day

Measurement speed: < 4 minutes for a 156 x 156 x 400 mm

standard brick

Range of lifetimes: 20 ns to several ms

Yield improvement: 1 mm cutting criteria for a

156 x 156 x 400 mm standard brick

Quality control: designed for quality monitoring of processes and materials like mono or multi-crystalline silicon

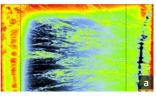
Contamination determination: metal (Fe) contaminations originated in crucibles and equipment

Reliability: modular and rugged industrial instrument for higher reliability and uptime > 99%

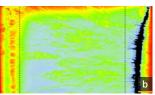
Repeatability: > 99.5%

Resistivity: resistivity mapping without frequent calibration

- Contactless and destruction free lifetime imaging (μPCD/ MDP (QSS), photoconductivity, resistivity and p/n check according to semi standard SEMI PV9-1110
- + Wafer cutting, Furnace monitoring, Material optimization and more



a. Lifetime (t) map of multi-crystalline Si brick with automated determination of cut criteria



b. Spatially resolved p/n conduction type transformation detection

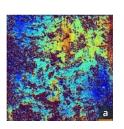


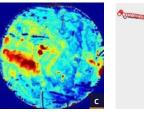
c. Resistivity map of multicrystalline Si brick

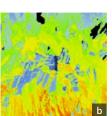
Sophisticated Material Research & Development

Few examples for research applications

- + Iron concentration determination
- + Trap concentration determination
- + Boron oxygen determination
- + Injection dependent measurements and more









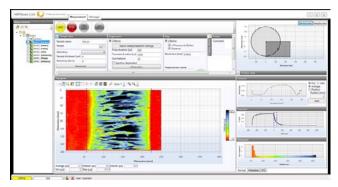


- c. Relative boron oxygen, density map
- d. Injection dependent lifetime curves with trapping

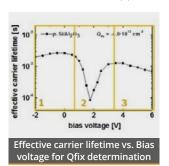
MDPStudio

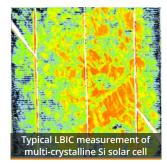
User-friendly and advanced operating software with:

- > Export and import functions
- > User structure with operator
- > Overview over all performed measurements
- > Sample parameter input
- > Single point measurements e.g. injection dependent measurements
- > Mapping options
- > Recipes
- > Package of analysis functions
- > View of linescans and single transients



Remote accessibility: IP based system allows remote operation and technical support from anywhere in the world.





Relevant products





Configuration options

- > Spot size variation
- Resistivity measurement (bricks/wafers)
- > Reference wafer
- > Sheet resistance
- > Background/Bias light
- > Reflection measurement (MDP)
- > LBIC
- > BiasMDP
- > LBIC, BiasMDP measurement stage with contacts
- > Internal iron mapping of Si
- > P/N detection
- > Bar code reader
- > Wide range of lasers

Technical specifications

Sample size **Brick**

> between 125 x 125 to 210 x 210 mm², maximum brick length: 500 mm

Wafer

up to 300 mm diameter (standard), up to 450 mm diameter (on request),

down to 5 x 5 mm

Range of lifetimes

20 ns to several ms

Resistivity

 $0.2 - > 10^3$ Ohm cm

Conduction

type

Measureable properties

lifetime - µPCD/MDP (QSS), photoconduc-

tivity

p, n

Excitation

select up to four different wavelengths from

355 nm up to 1480 nm. 980 nm (default)

Laptop or PC

Windows 7 or latest, .NET Framework

requirements update, 2 Ethernet ports

Power

100 - 250 V AC, 6 A

requirements

Dimensions 1000 x 720 x 1500 mm

Weight

ca. 200 kg

Certification

manufactured under ISO 9001

guidelines, CE conform

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DIN EN ISO 9001



